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What is claimed is:

- A thermally controlled apparatus for lining a processing chamber comprising:
 - a base:
 - an inner wall connected to the base; and,
- a passage disposed in the base, the inner wall or the base and the inner wall, the passage having an inlet and outlet.
- 2. The apparatus of claim 1 further comprising an outer wall connected to the base
- 3. The apparatus of claim 2 wherein the outer wall further comprises a pumping port.
- The apparatus of claim 1 wherein the inner wall further comprises a magnet disposed in the inner wall.
- 5. The apparatus of claim 1 wherein the base is comprised of a material selected from the group of aluminum, ceramic and stainless steel.
- 6. The apparatus of claim 1 further comprising:
- a first and second boss projecting from the base, the first boss comprising a hole in fluid communication with the passage at the inlet, and the second boss comprising a hole in fluid communication with the passage at the outlet.
- A thermally controlled apparatus for lining a processing chamber comprising:
 - a center member:
 - a flange circumscribing the center member;
- a cylindrical wall projecting from the center member inside of the flange; and

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a passage disposed in the center member having an inlet and an outlet

- 8. The apparatus of claim 7 further comprising:
- a lid disposed opposite the cylindrical wall, the lid and the wall defining a plenum at least partially therebetween.
- 9. The apparatus of claim 8 wherein the center member further comprises:
- a plurality of nozzles disposed in the center member providing fluid access to the plenum.
- 10. The apparatus of claim 8 further comprising:
- a gas feedthrough fluidly coupled to the plenum through a hole disposed in the lid.
- 11. A thermally controlled apparatus for lining a processing region defined at least partially by sidewalls and a bottom of a processing chamber, comprising:
 - a liner adapted to be removably disposed in the processing region; and
- a passage disposed at least partially in the liner and adapted to fluidly isolate a heat transfer fluid flowing therethrough from the process volume.
- 12. The apparatus of claim 11, wherein the liner comprises:
- a base adapted to be disposed adjacent the bottom of the chamber, at least a portion of the passage defined between the base and the bottom of the chamber.
- 13. The apparatus of claim 12, wherein the liner further comprises:
- a first boss and a second boss projecting from the base, the first boss comprising a hole in fluid communication with the passage at an inlet of the passage, and the second boss comprising a hole in fluid communication with the passage at an outlet of the passage.

- 14. The apparatus of clam 12, wherein the passage is a channel formed in a surface of the base and is adapted to be enclosed by the bottom of the chamber.
- 15. The apparatus of claim 11, wherein the liner comprises a cylindrical wall
- 16. The apparatus of claim 15, wherein the passage is formed at least partially in the cylindrical wall.
- 17. The apparatus of claim 15, wherein the cylindrical wall comprises a lip extending into the process volume.
- 18. The apparatus of claim 15, wherein the cylindrical wall comprises a magnet disposed therein.
- 19. The apparatus of claim 15, wherein the cylindrical wall comprises:
 - a lip extending to the process volume; and
 - a magnet disposed therein.
- 20. The apparatus of claim 15, wherein the cylindrical wall is configured to line the sidewalls of the chamber
- 21. The apparatus of claim 15, wherein the cylindrical wall is configured to line a substrate support disposed in the process volume of the chamber.
- 22. The apparatus of claim 11, wherein the liner further comprises:
 - an outer cylindrical wall:
 - an inner cylindrical wall; and
- a bottom coupled between the outer cylindrical wall and the inner cylindrical wall.

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- 23. The apparatus of claim 11, wherein the liner is comprised of a material selected from the group of aluminum, ceramic and stainless steel.
- 24. The apparatus of claim 11, wherein the liner comprises: a textured interior surface adapted to be exposed to the interior volume.
- 25. A thermally controlled apparatus for lining a processing region defined at least partially by sidewalls and a bottom of a processing chamber, comprising:

an annular base having a perimeter;

- a first cylindrical wall extending from the perimeter of the base; and a passage disposed at least partially in the base.
- 26. The apparatus of claim 25, wherein the passage is adapted to isolate a heat transfer fluid flowing therethrough from the process volume.
- 27. The apparatus of claim 25, wherein the base further comprises:
- a first boss and a second boss projecting from the base, the first boss comprising a hole in fluid communication with the passage at an inlet of the passage, and the second boss comprising a hole in fluid communication with the passage at an outlet of the passage.
- 28. The apparatus of clam 25, wherein the passage is a channel formed in a surface of the base and is adapted to be enclosed by the bottom of the chamber.
- 29. The apparatus of claim 25, wherein the first cylindrical wall comprises a lip extending radially inwards in a spaced-apart relation to the base.
- 30. The apparatus of claim 25 further comprising a second cylindrical wall coupled to an inner portion of the base.

- 31. The apparatus of claim 25, wherein the base and first cylindrical wall are comprised of a material selected from the group of aluminum, ceramic and stainless steel.
- 32. The apparatus of claim 25, wherein the first cylindrical wall comprises a textured inner surface.
- 33. A thermally controlled apparatus for lining a processing region defined at least partially by sidewalls and a bottom of a processing chamber, comprising:
 - an annular base:
 - a first cylindrical wall coupled to an outer portion of the base;
 - a second cylindrical wall coupled to an inner portion of the base; and,
 - a passage disposed at least partially in the base.
- 34. The apparatus of claim 33 further comprising at least one ridge extending between the first cylindrical wall and the second cylindrical wall in a spaced-apart relation to the base.
- 35. The apparatus of claim 33, wherein the passage is at least partially disposed in at least one of the first or second cylindrical walls.
- 36. A thermally controlled apparatus for lining a processing region at least partially defined by walls of a processing chamber, comprising:
- a cylindrical wall adapted to line at least a portion of the walls of the processing chamber:
 - a center member coupled to one end of the cylindrical wall; and
 - a passage at least partially disposed in the center member.
- 37. A thermally controlled apparatus for lining a processing region at least partially defined by walls of a processing chamber, comprising:
- a center member having a first side adapted to be exposed to the processing region;

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- a cylindrical wall extending from the first side of the center member and adapted to line at least a portion of the walls of the processing chamber; and
- a passage at least partially disposed in the center member, the passage adapted to isolate a heat transfer fluid flowing therethrough from the processing volume.
- 38. The apparatus of claim 37 further comprising a lid disposed proximate the center member and defining a plenum at least partially therewith.
- 39. The apparatus of claim 38, wherein the center member further comprises a plurality of nozzles disposed in the center member providing fluid access between the plenum and a side of the center member opposite the lid.